

2016 Applied Materials Technical Symposiums in Taiwan

Exploring New Non-Volatile Memories and Logic beyond 10nm

March 23 2016, Ambassador Hsinchu Hotel, Ballroom A

Time	Title	Presenter
13:30 – 13:45	Welcome	Nelson Chai, Applied Materials
13:45 – 14:20	Future Logic Devices	Prof. Chenming Hu, UC Berkeley
14:20 – 14:55	Gate-All-Around(GAA): Challenges and Opportunities	Hans Mertens, IMEC
14:55 – 15:20	Field-effect Transistor Technology Solutions for Sub-7nm	Nam Sung Kim, Applied Materials
15:20 – 15:35	Break	
15:35 – 16:00	Challenges and Opportunities In The Era of More-than-Moore (MTM)	Mike Rosa, Applied Materials
16:00 – 16:25	Using Data Analytics to Improve Process Tool Performance	Helen Armer, Applied Materials
16:25 – 16:40	Break	
16:40 – 17:15	Engineering Perpendicular Magnetic Tunnel Junctions for Embedded STT- MRAM through Materials and Process Co-optimization	Chando Park, Qualcomm
17:15 – 17:40	ReRAM and PCRAM e-NVM: Current Status and Future Direction	Er-Xuan Ping, Applied Materials
17:40 – 18:05	Endura PVD System for Emerging Memory Technology	Kevin Moraes, Applied Materials
18:05 – 18:10	Conclusion	Jackie Tan, Applied Materials

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March 24 2016, Tainan Science Park SIAT/SMEA Lecture Hall B101

Time	Title	Presenter
11:00 – 11:15	Welcome	Jackie Tan, Applied Materials
11:15 – 11:50	Future Logic Devices	Prof. Chenming Hu, UC Berkeley
11:50 – 12:50	Lunch	
12:50 – 13:25	Engineering Perpendicular Magnetic Tunnel Junctions for Embedded STT- MRAM through Materials and Process Co-optimization	Chando Park, Qualcomm
13:25 – 13:50	Endura PVD System for Emerging Memory Technology	Kevin Moraes, Applied Materials
13:50 – 14:15	Interconnect Solutions for 10nm and Beyond	Kavita Shah, Applied Materials
14:15 – 14:30	Break	
14:30 – 15:05	Gate-All-Around(GAA): Challenges and Opportunities	Hans Mertens, IMEC
15:05 – 15:30	Implant Solutions for Contact Resistivity Reduction for CMOS 10nm node and Beyond	Vivek Rao, Applied Materials
15:30 – 15:55	Field-effect Transistor Technology Solutions for 10nm And Beyond	Nam Sung Kim, Applied Materials
15:55 – 16:20	Challenges and Opportunities In The Era of More-than-Moore (MTM)	Mike Rosa, Applied Materials
16:20 – 16:25	Conclusion	Jackie Tan, Applied Materials